UNITED STATES PATENT AND TRADEMARK OFFICE CERTIFICATE OF CORRECTION

PATENT NO. : 7,170,683 B2 Page 1 of 1

APPLICATION NO.: 10/510725
DATED: January 30, 2007
INVENTOR(S): Minoru Sugawara

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

Title Page:

Item (54) should be read as follows:

-- REFLECTOR FOR EXPOSURE LIGHT AND ITS MANUFACTURE METHOD, MASK, EXPOSURE APPARATUS AND SEMICONDUCTOR DEVICE MANUFACTURE METHOD --.

Signed and Sealed this

Seventh Day of August, 2007

JON W. DUDAS
Director of the United States Patent and Trademark Office